

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of the claims in the application:

Listing of Claims:

1. (Currently Amended) A chemical vapor deposition system comprising: a first cleaning gas source fluidly coupled to a chemical vapor deposition chamber through a first cleaning gas distribution channel disposed within a lid of the chemical vapor deposition chamber, the lid further supporting a shower head disposed within the chemical vapor deposition chamber, said showerhead fluidly coupled to processing gas plumbing for introducing processing gasses to said chemical vapor deposition chamber and separate separately from the first cleaning gas distribution channel, the cleaning gas distribution channel being separate from the showerhead, said lid having an interior rim including a plurality of cleaning gas injection ports, each of which is fluidly connected to the first cleaning gas distribution channel, and various ones of which are oriented at different angles with respect to an interior of a wall of the chemical vapor deposition chamber, said wall being attached to said lid, wherein the plurality of cleaning gas injection ports include a first subset of the plurality of cleaning gas injection ports disposed at a first angle relative to the interior of the wall of the chemical vapor deposition chamber, and a second subset of the plurality of cleaning gas injection ports disposed at a second angle relative to the interior of the wall.

2 - 6. (Cancelled)

7. (Currently Amended) The chemical vapor deposition system of claim 1, further including internal plumbing coupling the first cleaning gas distribution channel to the first cleaning gas source within the wall of the chemical vapor deposition chamber.

8. (Currently Amended) The chemical vapor deposition system of claim ~~1~~ 7, further including a plurality of channel openings coupling the internal plumbing to the cleaning gas distribution channel.

9. (Currently Amended) The chemical vapor deposition system of claim 1, further including a chamber collar separating the lid of the chemical vapor deposition chamber from the wall of the chemical vapor deposition system and including internal plumbing coupling the cleaning gas distribution channel to the first cleaning gas source.

10 - 21. (Cancelled)